

Notice of References Cited	Application/Control No. 10/813,079		Applicant(s)/Patent Under Reexamination FUJIMOTO, KIWAMU	
	Examiner George A. Goudreau		Art Unit 1763	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,033,827	03-2000	Itani, Toshiro	430/270.1
*	B	US-5,316,616	05-1994	Nakamura et al.	438/713
*	C	US-6,670,265	12-2003	Wang et al.	438/624
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP 63-160,227	07-1988	Japan	Sagawa	-----
	O	JP 2000-036,484	02-2000	Japan	Shimizu et. al.	-----
	P	JP 2002-145,955	05-2002	Japan	Tsutsumi et. al.	-----
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Study of Dry Etching Resistance of Methacrylate Polymers for ArF Excimer Laser Lithography"; Proceedings of SPIE (1998); volume 3333 (pt. 1); Ohfuji et. al.; pp. 595-600
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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